



NOEL Technologies

## ADVANCED STEPPER LITHOGRAPHY SERVICES

### ASML PAS 5500/300:DUV (248nm) 0.25nm Resolution

#### Features

Wafer Diameter	6"
Minimum Feature	0.25 $\mu$ m, Overlay <75nm
22mm x 22mm field size, max rectangle 14.7mm x 27.4mm	
Stitching (<75nm) for full wafer devices	
Illumination control of coherence for conventional and annular settings	
NA range	0.40 to 0.63
6" Reticles, 4x reduction	

